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Examiner Initial	PUBLICATION		
GH	5	"SU-8: A Thick Photo-Resist for MEMS" SOTECm website: Introduction; Physical Properties; Other Properties; Process Tips; Research Links; Commercial Solutions; Literature Reference (created 01/99 – modified 2/22/2001) – http://aveclafaux.freesevers.com/SU-8.html (printed 9/11/2001 – pages 1-11)	
GH	6	MicroChem Product Information Sheet "SU-8 Resists" Product Attributes; Additional Benefits of SU-8 2000; Applications for SU-8 and SU-8 2000. ©2001, MicroChem Corp. http://www.microchem.com/products/su_eight.htm (printed 9/12/2001- pg 1 of 1)	
GH	7	MicroChem Product Information Sheet "SU-8 Resists - FAQs" ©2001, MicroChem Corp http://www.microchem.com/products/su_eight_faq.htm (printed 9/12/2001 – pages 1-2)	
GH	8	MicroChem Product Information: NANO™ SU-8 Negative Tone Photoresists Formulations 50 & 100 (4 pages) ©2001, MicroChem Corp., 1254 Chestnut Street, Newton, MA 02464.	
GH	9	MicroChem Product Information: NANO™ SU-8 Negative Tone Photoresists Formulations 2 - 25 (4 pages) ©2001, MicroChem Corp., 1254 Chestnut Street, Newton, MA 02464.	
GH	10	Shaw, J.M., et al. "Negative Photoresists for Optical Lithography". 0018-8646/97 © 1997 IBM, pages 1-16. http://www.research.ibm.com/journal/rd/411/shaw.txt (printed 10/20/2001)	
Examiner	Date Considered		
Cynthia Hamlin	3-9-03		
*Examiner: initial reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant. (Applicants' substitute for PTO Form PTO/SB08B) Attorney Dkt No. 20206-14/#167131			

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